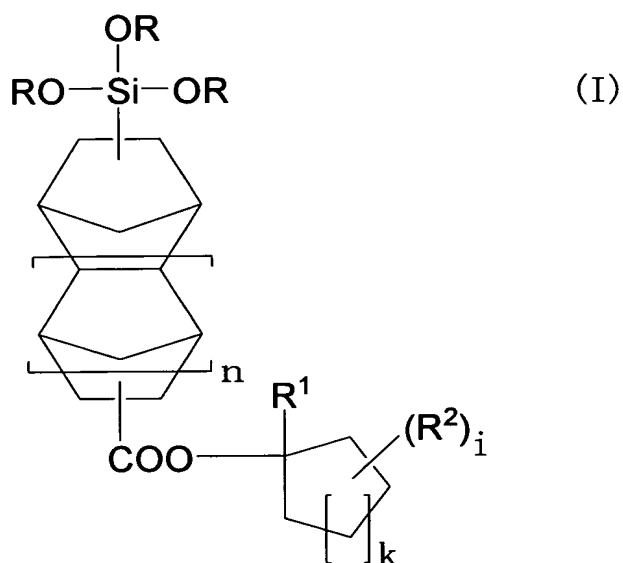


ABSTRACT OF THE DISCLOSURE

A novel polysiloxane suitable as a resin component of a chemically-amplified resist exhibiting particularly excellent I-D bias, depth of focus (DOF), and the like, a novel silane compound useful as a raw material for synthesizing the polysiloxane, and a radiation-sensitive resin composition comprising the polysiloxane are provided.

The silane compound is shown by the following formula (I),



10

and the polysiloxane has a structural unit shown by the following formula (1),



5 10.

5 10.